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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/597,994	08/15/2006	Johan Hendrik Klootwijk	NL040148	8912
24737 7590 01/26/2009 PHILIPS INTELLECTUAL PROPERTY & STANDARDS P.O. BOX 3001 BRIARCLIFF MANOR, NY 10510			EXAMINER NHU, DAVID	
			ART UNIT 2895	PAPER NUMBER
			MAIL DATE 01/26/2009	DELIVERY MODE PAPER

**Please find below and/or attached an Office communication concerning this application or proceeding.**

The time period for reply, if any, is set in the attached communication.

<b>Office Action Summary</b>	<b>Application No.</b>		<b>Applicant(s)</b>	
	10/597,994		KLOOTWIJK ET AL.	
	<b>Examiner</b>		<b>Art Unit</b>	
	DAVID NHU		2895	

**-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --**

**Period for Reply**

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period **will** apply and **will** expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply **will**, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

**Status**

- 1) ☒ Responsive to communication(s) filed on 15 August 2006.
- 2a) ☐ This action is **FINAL**.                      2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

**Disposition of Claims**

- 4) ☒ Claim(s) 1-9 is/are pending in the application.
- 4a) Of the above claim(s) \_\_\_\_\_ is/are withdrawn from consideration.
- 5) ☐ Claim(s) \_\_\_\_\_ is/are allowed.
- 6) ☒ Claim(s) 1,8 and 9 is/are rejected.
- 7) ☒ Claim(s) 2-7 is/are objected to.
- 8) ☐ Claim(s) \_\_\_\_\_ are subject to restriction and/or election requirement.

**Application Papers**

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on \_\_\_\_\_ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.  
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).  
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

**Priority under 35 U.S.C. § 119**

- 12) ☒ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☒ All    b) ☐ Some \*    c) ☐ None of:
1. ☒ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.
3. ☒ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

\* See the attached detailed Office action for a list of the certified copies not received.

**Attachment(s)**

- |  |   |
|--|---|
| 1) <input checked="" type="checkbox"/> Notice of References Cited (PTO-892)            | 4) <input type="checkbox"/> Interview Summary (PTO-413)           |
| 2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948)   | Paper No(s)/Mail Date. _____                                      |
| 3) <input checked="" type="checkbox"/> Information Disclosure Statement(s) (PTO/SB/08) | 5) <input type="checkbox"/> Notice of Informal Patent Application |
| Paper No(s)/Mail Date <u>12/1/06</u> .   | 6) <input type="checkbox"/> Other: _____                          |

## **DETAILED ACTIONS**

1. Insert --This application is a 371 of PCT/IB05/50436 filed on 02/02/2005--

### **Specifications**

#### **Content of Specification**

2. The disclosure is objected to because of the following informalities: Field of the Invention, Description of the Related Art, and Brief Summary of the Invention, Brief Description of the Drawings, Detailed Description of the Invention are missing. Appropriate correction is required.

**Background of the Invention:** The specification should set forth the Background of the Invention in two parts:

- (a) **Field of the Invention:** A statement of the field of art to which the invention pertains. This statement may include a paraphrasing of the applicable U.S. patent classification definitions of the subject matter of the claimed invention. This item may also be titled "Technical Field."
- (b) **Description of the Related Art:** A description of the related art known to the applicant and including, if applicable, references to specific related art and problems involved in the prior art which are solved by the applicant's invention. This item may also be titled "Background Art."

3. The following guidelines illustrate the preferred layout and content for patent applications. These guidelines are suggested for the applicant's use.

### ***Arrangement of the Specifications***

The following order or arrangement is preferred in framing the specification and, except for the reference to "Microfiche Appendix" and the drawings, each of the lettered items should appear in upper case, without underlining or bold type, as section headings. If no text follows the section heading, the phrase "Not Applicable" should follow the section heading:

- (a) Title of the Invention.

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- (b) Cross-References to Related Applications.
- (c) Statement Regarding Federally Sponsored Research or Development.
- (d) Reference to a "Microfiche Appendix" (see 37 CFR 1.96).
- (e) Background of the Invention.
  - 1. Field of the Invention.
  - 2. Description of the Related Art including information disclosed under 37 CFR 1.97 and 1.98.
- (f) Brief Summary of the Invention.
- (g) Brief Description of the Several Views of the Drawing(s).
- (h) Detailed Description of the Invention.
- (i) Claim or Claims (commencing on a separate sheet).
- (j) Abstract of the Disclosure (commencing on a separate sheet).
- (k) Drawings.
- (l) Sequence Listing (see 37 CFR 1.821-1.825).

### **Abstract**

4. Submit a new abstract.

### ***Claim Rejections - 35 USC § 102***

5. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

6. Claims 1, 8, 9 are rejected under 35 U.S.C. 102 (b) as being anticipated by Okojie (6,248,646 B1), and Stoner et al (5,652,436).

**Regarding claim 1**, Okojie, (see figures 1-4, col. 2, lines 60-67, col.3, lines 1-67), teaches a method of making a comparatively small substrate 24 being processed in equipment designed for a larger standard substrate 20, wherein the standard substrate has a surface 22 in which a cavity 22 is formed, in which cavity, a small substrate 24 to be processed is attached by

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means of a bonding material layer 27, characterized in that, the cavity in the standard substrate is formed as so to have a flat bottom, which extends parallel to the surface (see figure 2), and a depth such that, after the small substrate is attached with a rear side to the flat bottom of the cavity in the surface of the standard substrate by means of said bonding material layer, a front side of said small substrate forms a free surface, which substantially coincides with the surface of the standard substrate (se figures 3-4).

**Regarding claim 1**, Stoner, (see figures 1-4, col. 4, lines 15-67, col.5-7, lines 1-67), teaches a method of making a comparatively small substrate 24 being processed in equipment designed for a larger standard substrate 22, wherein the standard substrate has a surface, in which a cavity is formed, in which cavity, a small substrate 26 to be processed is attached by means of a bonding material layer 27, characterized in that, the cavity in the standard substrate is formed as so to have a flat bottom, which extends parallel to the surface, and a depth such that, after the small substrate is attached with a rear side 26b to the flat bottom of the cavity in the surface of the standard substrate by means of said bonding material layer, a front side 26a of said small substrate forms a free surface, which substantially coincides with the surface of the standard substrate (se figure 4).

Regarding claims 8-9, Stoner, (see figures 1-4), teaches characterized in that the silicon substrate/wafer is provided at the polished rear side with aligning characteristics for the standard substrate in photolithographic process; and the silicon substrate is provided at the polished rear side with an etching mask formed in a silicon nitride layer 27.

### **Allowable Subject Matter**

5. Claims 2-7 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim

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and any intervening claims.

### **Conclusion**

6. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure: Malhi'911 is cited as of interest.

7. A shortened statutory period for response to this action is set to expired 3 (three) months and 0 (zero) day from the date of this letter. Failure to respond within the period for response will cause the application to become abandoned (see 710.02 (b)).

8. Any inquiry concerning this communication on earlier communications from the examiner should be directed to David Nhu, (571)272-1792.

The examiner can normally be reached on Monday-Friday from 7:30 AM to 5:00 PM. *The fax phone number for the organization where this application or proceeding is assigned is (571)273-8300.*

*Information regarding the status of an application may be obtained from the patent application information retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only.*

*For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).*

/David Nhu/ 1/18/2009 DN

Primary Examiner, Art Unit 2895